



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT application of:)	Art Unit:	2813	
Hisashi OHTANI et al.)	Examiner:	E. Pert	
Application No.:		08/807,737)	CERTIFICATE OF MAILING	
Filed:		February 27, 1997)	deposited with the U	t this correspondence is being Inited States Postal Service with
For:	r: METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICE)))	sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on <u>March 19,2001</u> Sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 2021, on <u>March 19,2001</u> Gusting J. Cantrell	

AMENDMENT AND RESPONSE TO RESTRICTION/ELECTION OF SPECIES REQUIREMENT

Commissioner of Patents Washington, D.C. 20231

March 19, 2001

Dear Sir:

In response to the Restriction and Election of Species Requirement mailed December 19, 2000, the period for responding having been extended two (2) months, Applicants hereby elect Species III, Claims 60-62, 72-74, 81, and 83, drawn to a method of disposing a catalyst metal on a silicon dioxide "wetting layer" to improve crystallization.

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